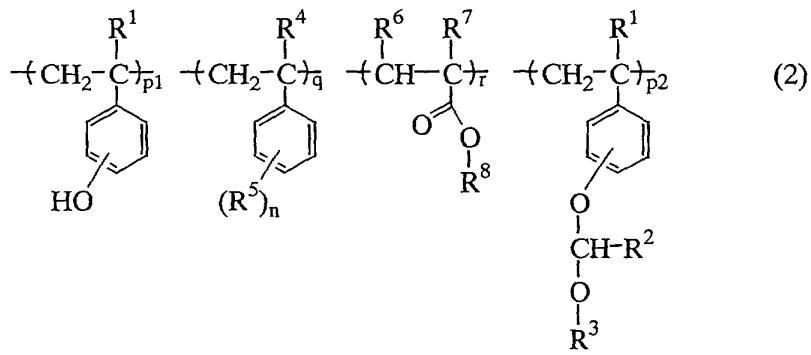
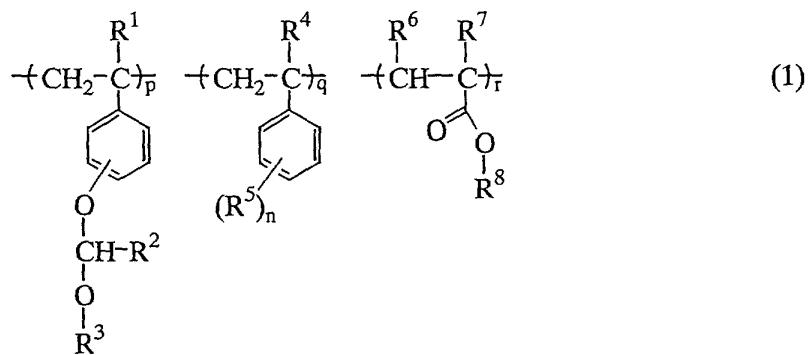


ABSTRACT

A polymer comprising recurring units of formula (2) is  
5 prepared by effecting deblocking reaction on a polymer  
comprising recurring units of formula (1) in the presence of  
an acid catalyst.



In the formulae, R<sup>1</sup> and R<sup>4</sup> are H or methyl, R<sup>2</sup> and R<sup>3</sup> are C1-C10 alkyl, or R<sup>2</sup> and R<sup>3</sup> may form a ring, R<sup>5</sup> is H, hydroxyl, alkyl, alkoxy or halogen, R<sup>6</sup> and R<sup>7</sup> are H, methyl, alkoxy carbonyl, cyano or halogen, R<sup>8</sup> is C4-C20 tertiary alkyl, n is an integer of 0 to 4, p is a positive number, q and r each are 0 or a positive number, exclusive of q=r=0, 10 p<sub>1</sub> is a positive number, p<sub>2</sub> is 0 or a positive number, and p<sub>1</sub>+p<sub>2</sub> = p. The polymer thus produced has a narrower molecular weight distribution than polymers produced by the prior art methods. A resist composition comprising the polymer as a base resin has advantages including a  
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dissolution contrast of resist film, high resolution, exposure latitude, process flexibility, good pattern profile after exposure, and minimized line edge roughness.